

DRAWINGS (Draft)

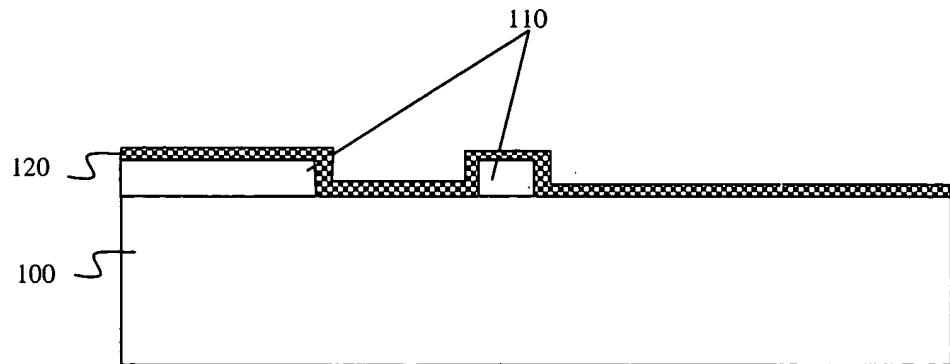


FIGURE 1a

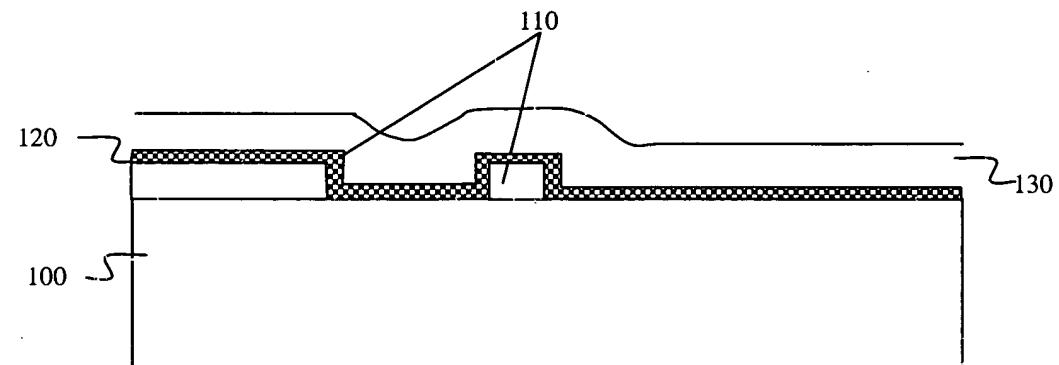


FIGURE 1b

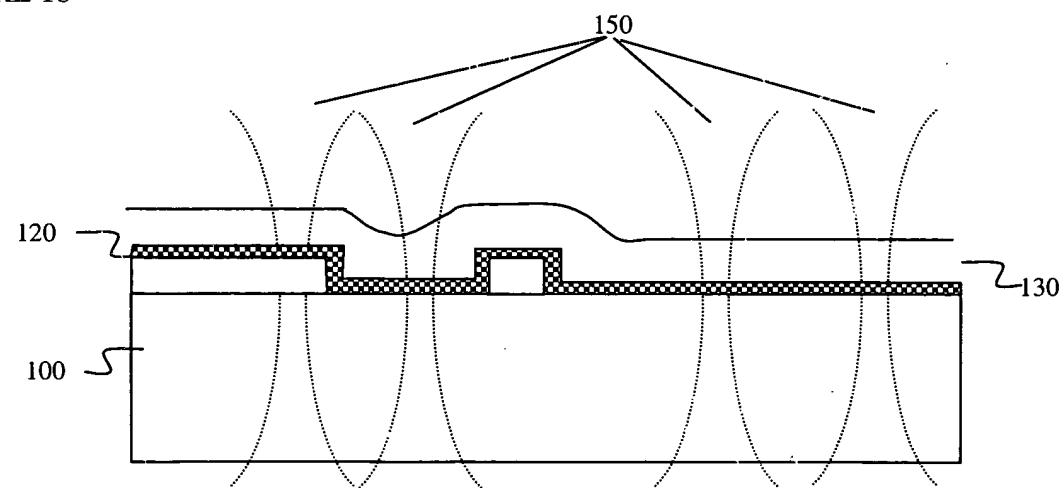


FIGURE 1c

Figure 1: Prior Art Lithography Processing

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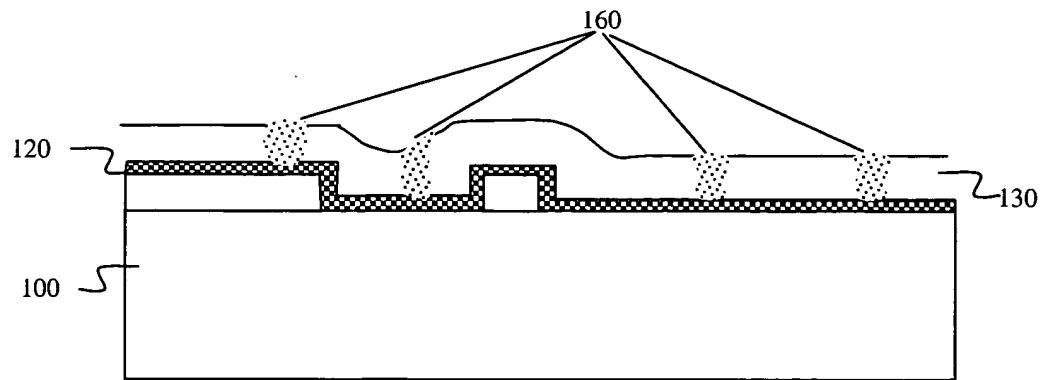


FIGURE 1d

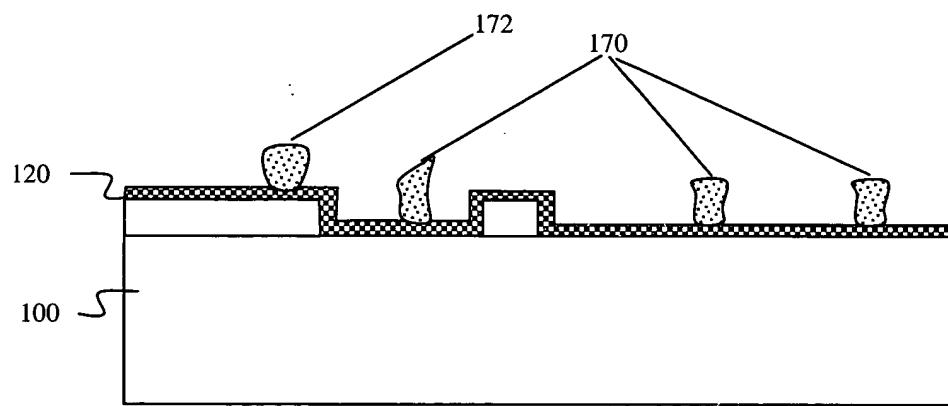


FIGURE 1e

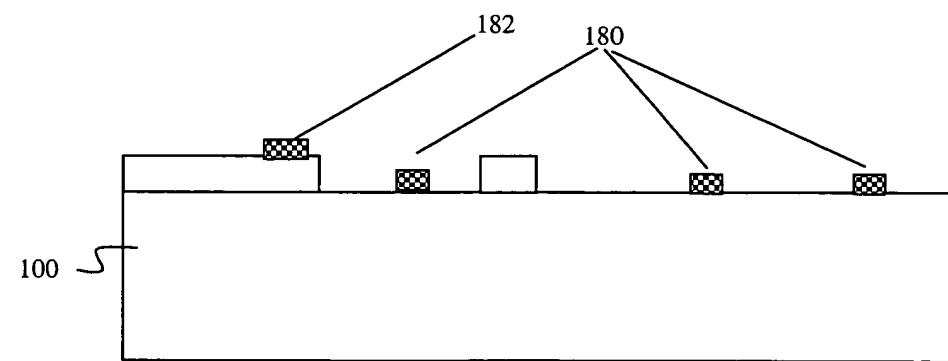


FIGURE 1f

Figure 1: Prior Art Lithography Processing

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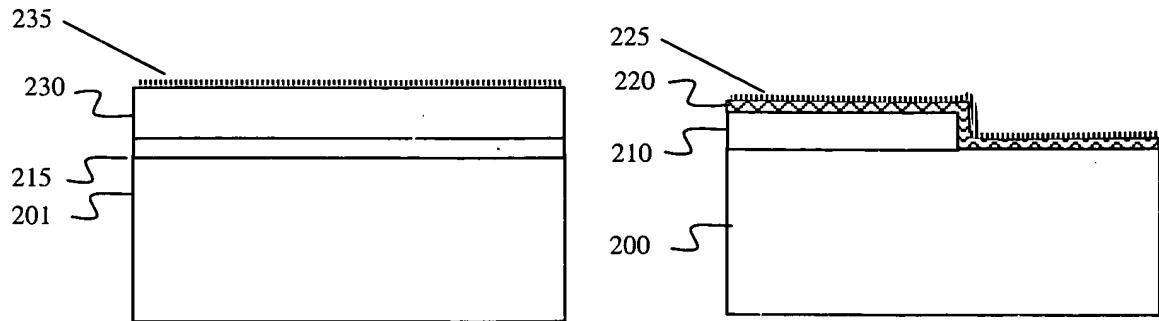


FIGURE 2a

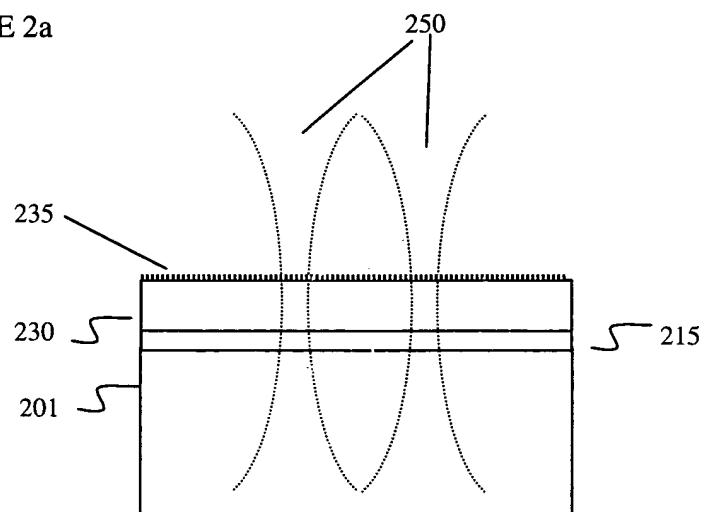


FIGURE 2b

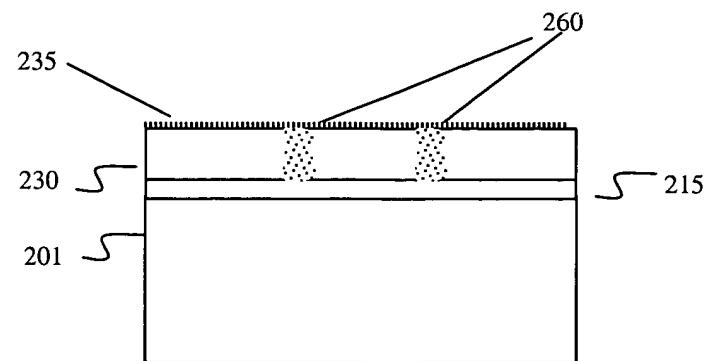


FIGURE 2c

DRAWINGS (Draft)

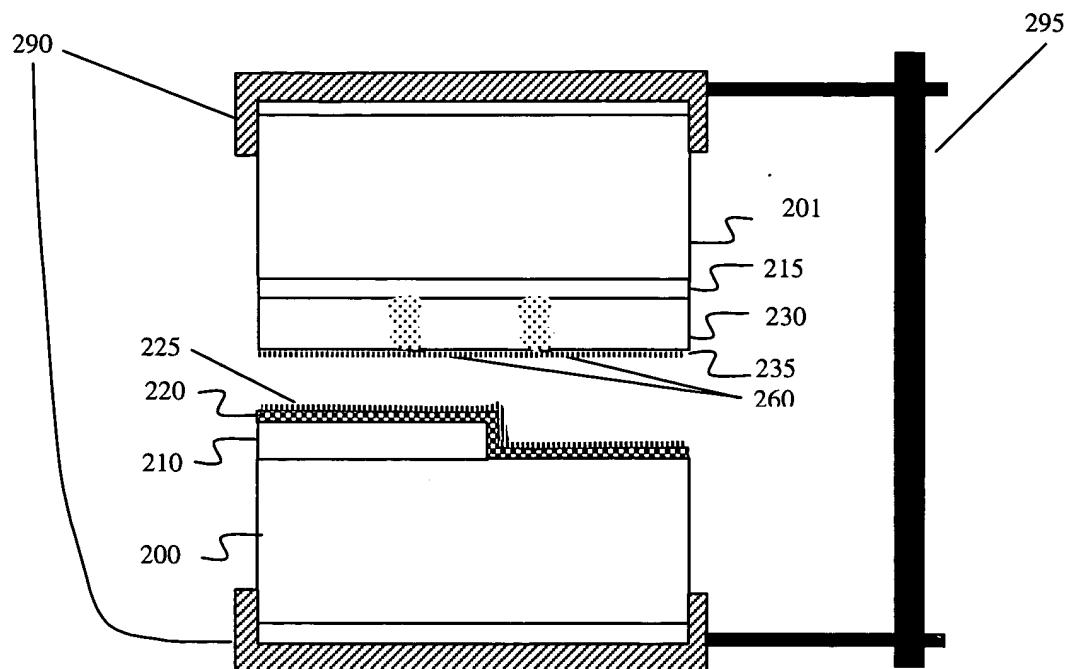


FIGURE 3a

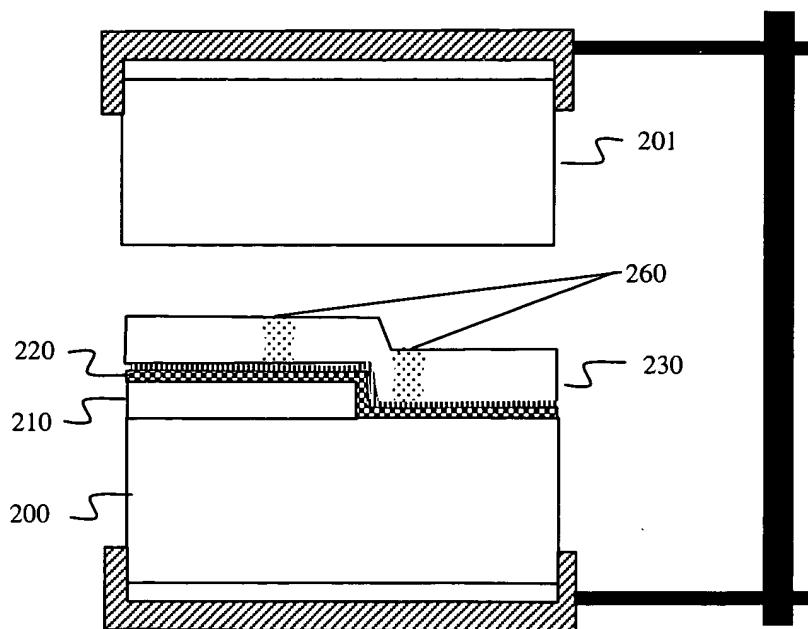


FIGURE 3b

DRAWINGS (Draft)

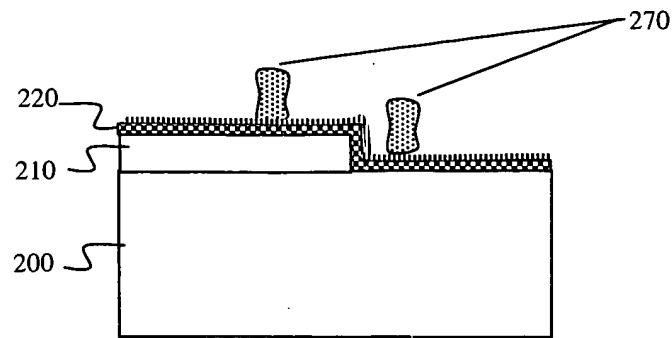


FIGURE 3c

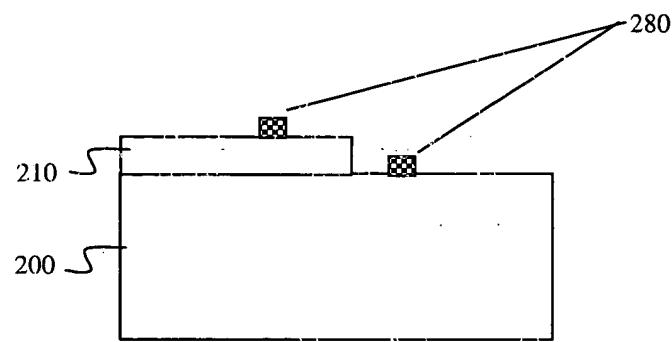


FIGURE 3d

DRAWINGS (Draft)

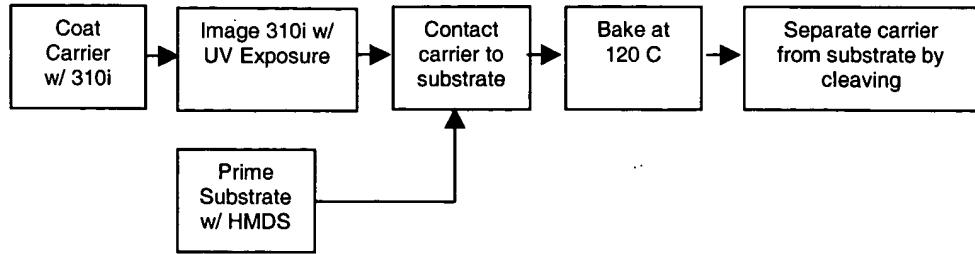


Figure 4a

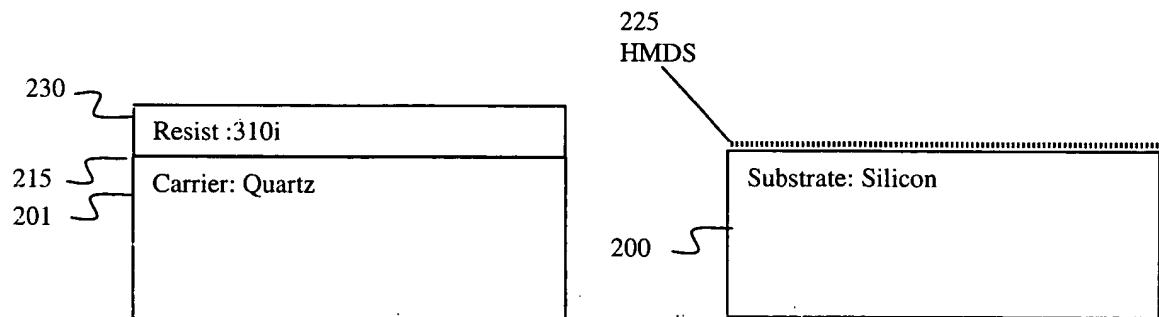


Figure 4b

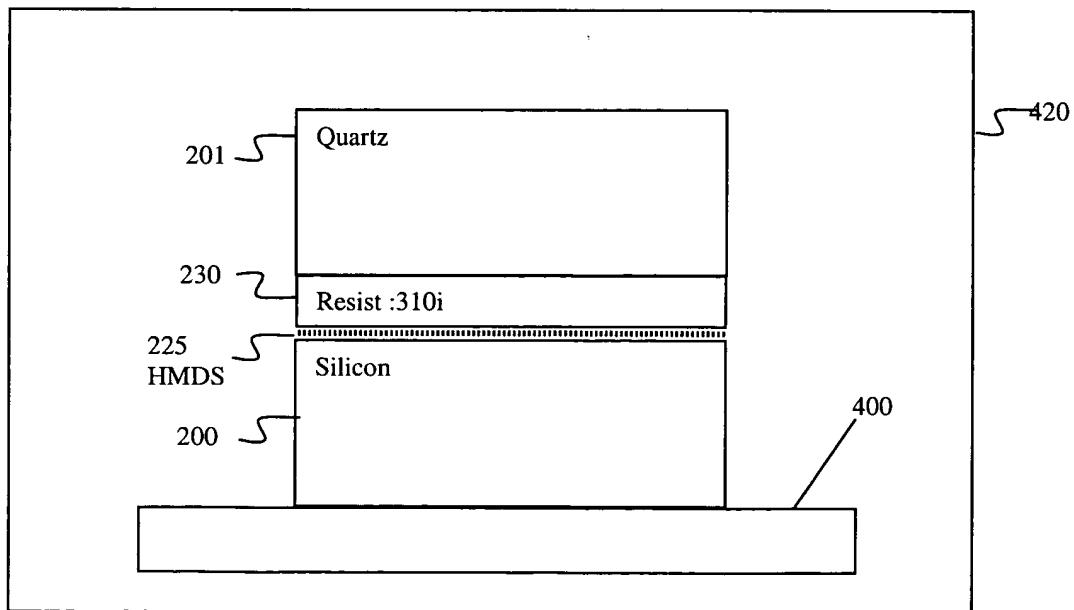


Figure 4c

DRAWINGS (Draft)

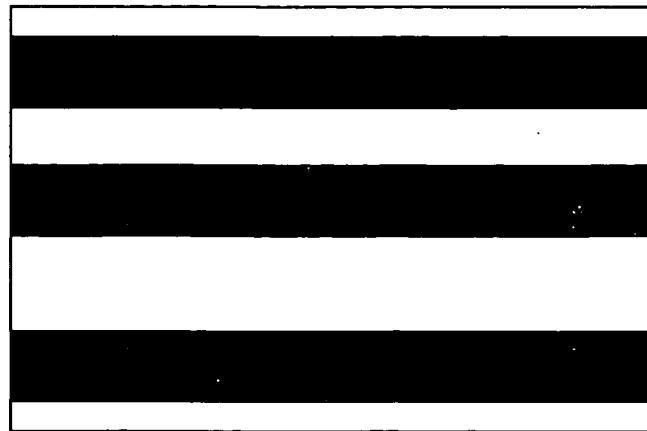


FIGURE 5: Mask Photo

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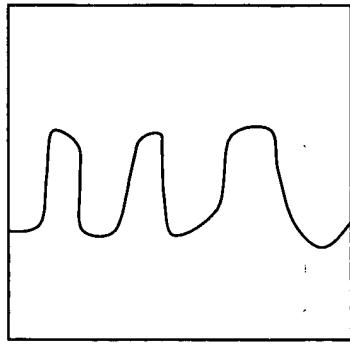


FIGURE 6a: Fringes before transfer

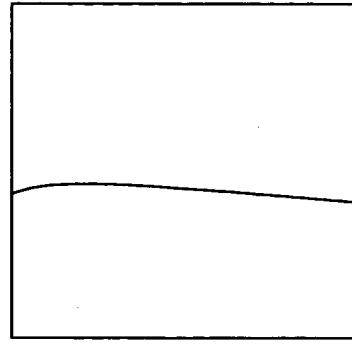
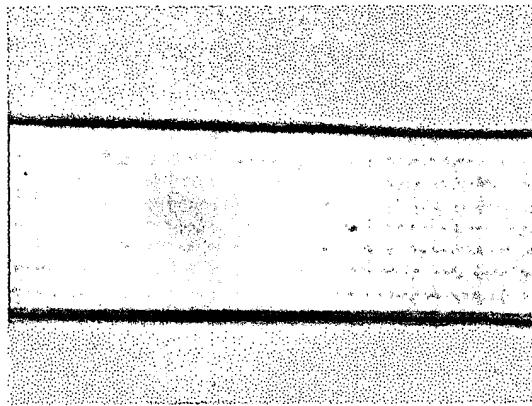


FIGURE 6b: Fringes after transfer

1 2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23 24 25 26 27 28 29 30 31 32 33 34 35 36 37 38 39 40 41 42 43 44 45 46 47 48 49 50 51 52 53 54 55 56 57 58 59 60 61 62 63 64 65 66 67 68 69 70 71 72 73 74 75 76 77 78 79 80 81 82 83 84 85 86 87 88 89 90 91 92 93 94 95 96 97 98 99 100

**DRAWINGS (Draft)**



**FIGURE 7: Developed Photoresist**

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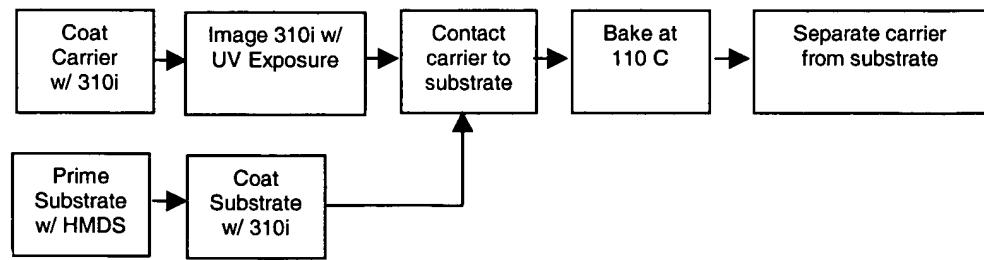


Figure 8a

230  
201  
225  
HMDS  
835  
Resist II: 310i  
Silicon  
200

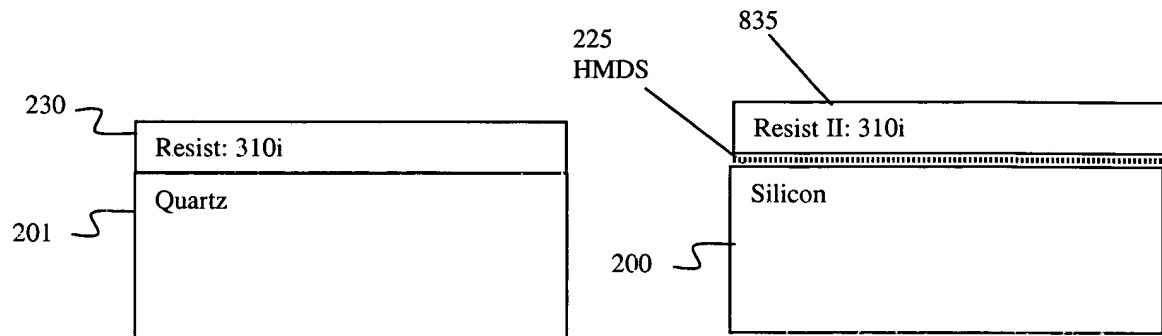


Figure 8b.

DRAWINGS (Draft)

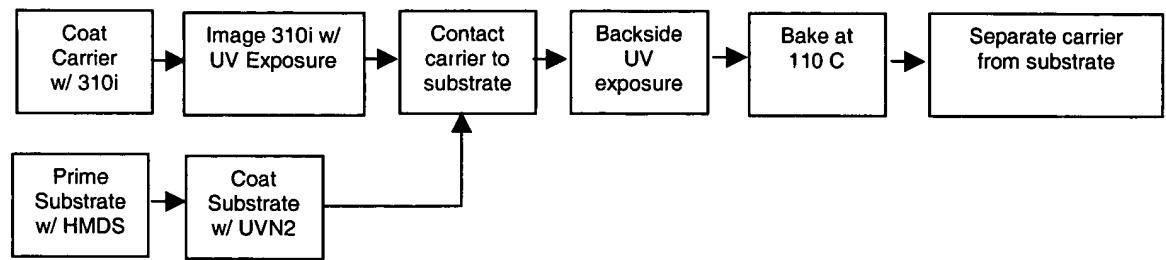


Figure 9a

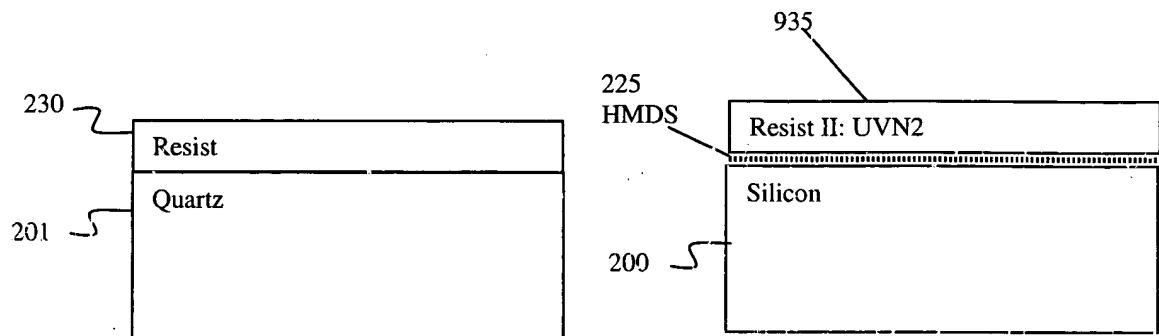


Figure 9b

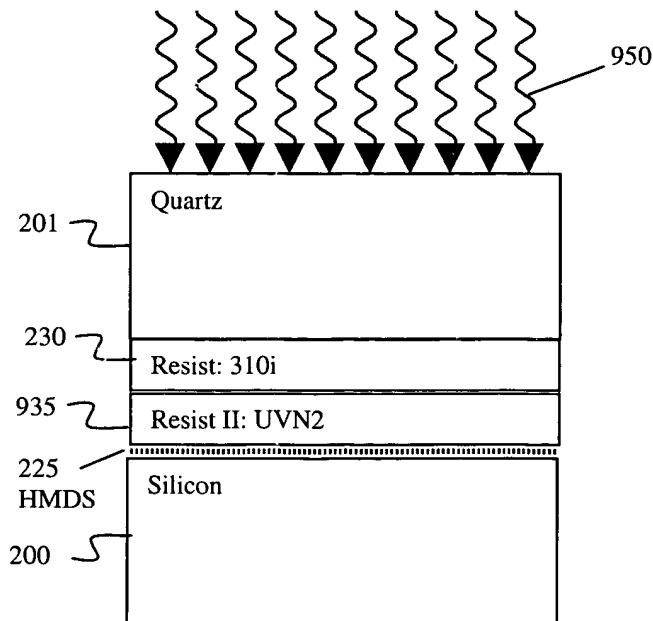


Figure 9c

DRAWINGS (Draft)

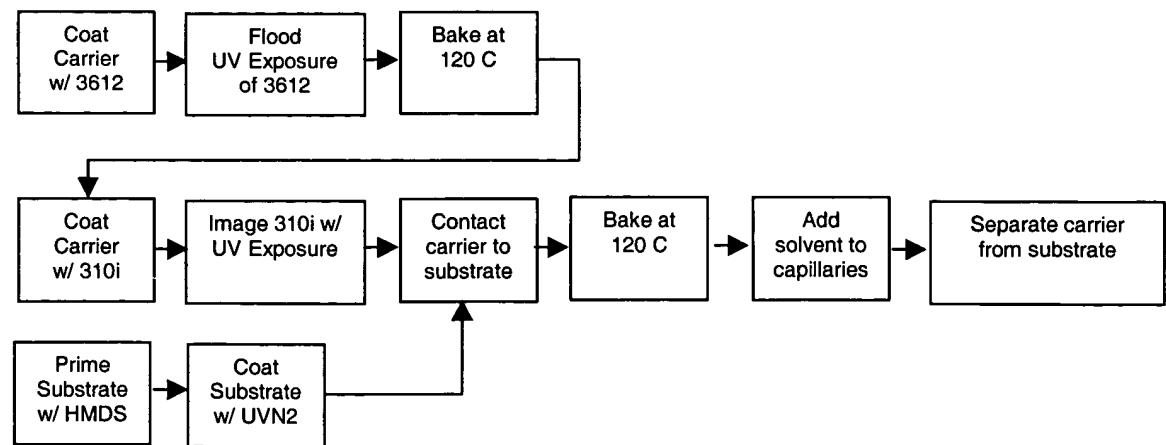


Figure 10a

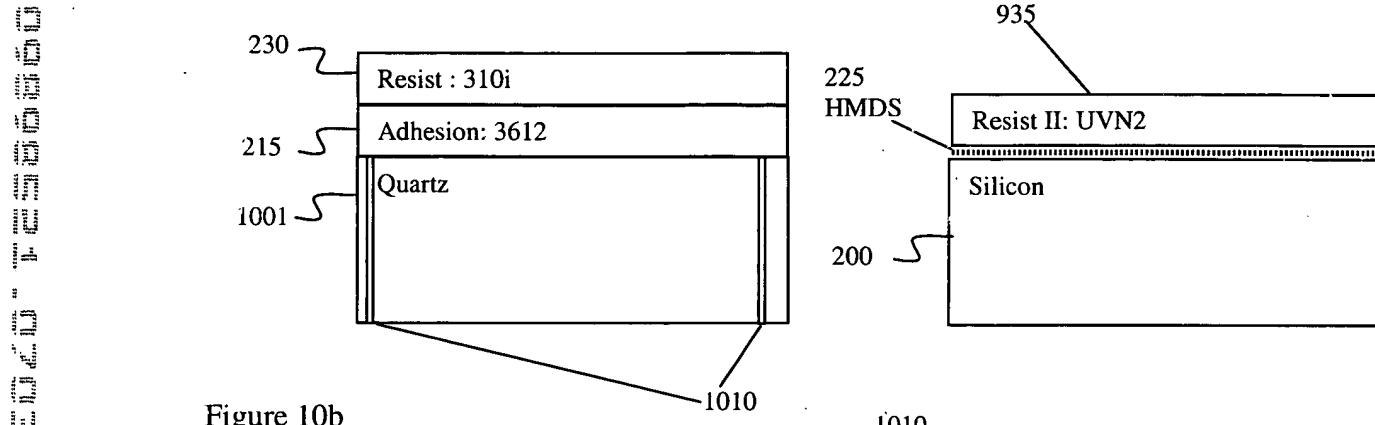


Figure 10b

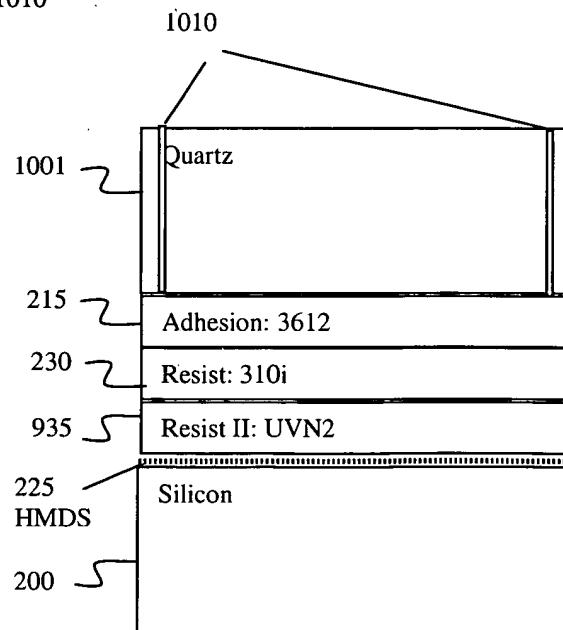


Figure 10c